

L Number	Hits	Search Text	DB	Time stamp
1	41	((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:34
2	74	oxide near2 (layer or film)) same (((ion near2 implant\$4) near5 (oxygen near ion)) same (through near5 (oxide near2 (layer or film)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:40
-	7066	((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:40
-	486	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:35
-	594	(soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:26
-	16042	locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:37
-	2	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:24
-	6	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:24
-	14	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:25

-	6	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)) same (trench\$2 or groove\$1 or open\$3 or hole)) and ((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:28
-	47	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)) same (trench\$2 or groove\$1 or open\$3 or hole)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:29
-	5	("4292091" "4319954" "4323417" "4338139" "4339285").PN.	USPAT	2004/08/12 14:31
-	20	4437225.URPN.	USPAT	2004/08/12 14:32
-	16	("4437225" "4683637" "4700454" "4810664" "5032535" "5114872" "5279978" "5418174" "5460983" "5482872" "5527719" "5610088" "5612239" "5612249" "5712173" "5733813").PN.	USPAT	2004/08/12 14:35
-	11	("4437225" "4863878" "4948742" "5182226" "5346841" "5441094" "5472902" "5488004" "5494846" "5707899" "5712186").PN.	USPAT	2004/08/12 14:37
-	107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:27
-	11	((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.) and ((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:41
-	62	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:54

51	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))) not (((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.) and ((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:44
5	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:53
12	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same oxidiz\$5) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:56
59	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same oxidiz\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:56
486	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:26
594	(soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:27
107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon) or (field near2 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 21:17
0	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:58
14	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:28
6	("5955767" "6100159" "6174754" "6403433" "6501133" "6515333").PN.	USPAT	2004/08/12 16:32
0	6724049.URPN.	USPAT	2004/08/12 16:33
1	6501133.URPN.	USPAT	2004/08/12 16:34
8	("5614729" "5920097" "5955767" "6100159" "6130457" "6174754" "6287901" "6303412").PN.	USPAT	2004/08/12 16:34

-	41	((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)) same (fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon) or (field near2 oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:58
-	107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon) or (field near2 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 21:18
-	92	(fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon) or (field near2 oxide)) near10 (sidewall\$1 near trench\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 21:45
-	18	(fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon) or (field near2 oxide)) near10 ((etch\$3 near5 sidewall\$1) near3 trench\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 21:46
-	995	oxide near2 (layer or film) same ((ion near2 implant\$4) near5 (oxygen near ion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:37
-	16042	locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:37
-	15	(oxide near2 (layer or film) same ((ion near2 implant\$4) near5 (oxygen near ion))) same (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:37
-	325	oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:36
-	49	(locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:44
-	8	(locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:44
-	41	((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:33

-	276	(oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:52
-	0	((oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 12:52